

INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Application No.	10/554,380	
	Filing Date	September 29, 2006	
	First Named Inventor	Hojo et al.	
	Art Unit	1795	
(Multiple sheets used when necessary)		Examiner	Anca Eoff
SHEET 1 OF 1		Attorney Docket No.	SHIGA7.032APC

U.S. PATENT DOCUMENTS					
Examiner Initials	Cite No.	Document Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear
	1	6,228,552	09-11-2001	Palmgren	
	2	US 2003/232273	12-18-2003	Adams et al.	
	3	US 2006/247346	11-02-2006	Hojo et al.	

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Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	T ¹
	4	JP H10-142799	05-29-1998	Toshiba Corp.		√ abstract
	5	JP 2001-056558	02-27-2001	Tokyo Ohka Kogyo Co., Ltd.		√
	6	JP 2003-295444	10-15-2003	Shiple Co., LLC		√
	7	JP 2004-333549	11-25-2004	Tokyo Ohka Kogyo Co., Ltd.		√ abstract
	8	JP 2002-323768	11-08-2002	Fuji Photo Film Co., Ltd.		√

NON PATENT LITERATURE DOCUMENTS				
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ¹	
	9	NAKAMURA et al., "Ultra Thin Film Resist for Low Energy E-beam Projection Lithography", Journal of Photopolymer Science and Technology, Vol. 15, No. 3, pp. 417-422, (2002)		
	10	YOSHIZAWA et al., "Comparative study of resolution limiting factors in electron beam lithography using the edge roughness evaluation method", Journal of Vacuum Science and Technology B, Vol. 19, Issue 6, pp. 2488-2493, (2001)		
	11	Office Action Issued on February 19, 2008, on the Japanese Patent Application No. 2003-334029.		
	12	Office Action Issued on February 19, 2008, on the Japanese Patent Application No. 2003-347136.		

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Examiner Signature	Date Considered
<p>*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>	

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